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2	L2	1	L1 and (plasma same ((HF same LF) (dual duel) adj frequency (low adj frequency same high adj frequency)))	USPAT	2007/11/23 19:14

on Hotel Computer
10/807,680

2

3	L3	22	(porous near5 dielectric) and (plasma same ((HF same LF) (dual duel) adj frequency (low adj frequeney same high adj frequency)))	USPAT	2007/11/23 19:14
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L6

3

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4

6	L6	65	(porous near5 dielectric) and (plasma same ((HF same LF) (dual duel) adj frequency (low adj frequeny same high adj frequency)))	US - PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/11/23 19:15 .
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5

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7	L7	1	L1 and (plasma same ((HF same LF) (dual duel) adj frequency (low adj frequency same high adj frequency)))	US-PGPUB; USPAT; USOCR	2007/11/23 19:15

Day : Friday
Date: 11/23/2007

Time: 18:12:10

PALM INTRANET**Inventor Information for 10/807680**

Inventor Name	City	State/Country
WU, QINGGUO	TUALATIN	OREGON
FU, HAIYING	WEST LINN	OREGON
MUIR, TIMOTHY J.	TIGARD	OREGON

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PALM INTRANET**Inventor Name Search Result**

Your Search was:

Last Name = WU

First Name = QINGGUO

Application#	Patent#	Status	Date Filed	Title	Inventor Name
10624959	7112615	150	07/22/2003 IDS	POROUS MATERIAL FORMATION BY <u>CHEMICAL VAPOR DEPOSITION ONTO COLLOIDAL CRYSTAL TEMPLATES</u>	WU, QINGGUO
10672311 IDS	7208389	150	09/26/2003	METHOD OF POROGEN REMOVAL FROM POROUS LOW-K FILMS USING UV RADIATION	WU, QINGGUO
10789103 IDS	Not Issued	41	02/27/2004	Methods for producing low-k CDO films with low residual stress	WU, QINGGUO
10800409 IDS	Not Issued	100	03/11/2004	METHODS FOR PRODUCING LOW-K CDO FILMS	WU, QINGGUO
10807680	Not Issued	30	03/23/2004	Methods of porogen removal for porous low dielectric constant films using plasma treatments	WU, QINGGUO
10820525 IDS	Not Issued	41	04/07/2004	Methods for producing low-k CDO films with low residual stress	WU, QINGGUO
10849568 IDS	Not Issued	71	05/18/2004	Method for improving mechanical properties of low dielectric constant materials	WU, QINGGUO
10927777 IDS	7241704	150	08/27/2004	METHODS FOR PRODUCING LOW STRESS POROUS LOW-K DIELECTRIC MATERIALS USING PRECURSORS WITH ORGANIC FUNCTIONAL GROUPS	WU, QINGGUO
10941502 IDS	Not Issued	99	09/14/2004	METHODS FOR IMPROVING INTEGRATION PERFORMANCE OF LOW STRESS CDO FILMS	WU, QINGGUO

<u>11369658</u> <i>JDS</i>	Not Issued	30	03/06/2006	Methods for fabricating high hardness/modulus low dielectric constant materials	WU, QINGGUO
<u>11608056</u> <i>JDS</i>	Not Issued	30	12/07/2006	PECVD METHODS FOR PRODUCING ULTRA LOW-K DIELECTRIC FILMS USING UV TREATMENT	WU, QINGGUO
<u>11693661</u> <i>JDS</i>	Not Issued	30	03/29/2007	METHODS FOR IMPROVING PERFORMANCE OF ODC FILM WITH DIELECTRIC CONSTANT < 4.0	WU, QINGGUO
<u>11764750</u> <i>No place or date in previous row</i>	Not Issued	41	06/18/2007	METHODS FOR PRODUCING LOW STRESS POROUS LOW-K DIELECTRIC MATERIALS USING PRECURSORS WITH ORGANIC FUNCTIONAL GROUPS	WU, QINGGUO
<u>11936752</u> <i>3m dep. meth ch not prev</i>	Not Issued	19	01/01/0001	METHODS FOR IMPROVING INTEGRATION PERFORMANCE OF LOW STRESS CDO FILMS	WU, QINGGUO
<u>11936754</u> <i>all prev</i>	Not Issued	19	01/01/0001	METHODS FOR PRODUCING LOW-K CDO FILMS	WU, QINGGUO
<u>60397747</u>	Not Issued	159	07/22/2002	Chemical vapor deposition onto colloidal crystal templates	WU, QINGGUO
<u>60524330</u>	Not Issued	159	11/20/2003	Methods for producing low-k CDO film of low residue stress with dielectric constant < 3.0	WU, QINGGUO
<u>60852635</u>	Not Issued	160	10/17/2006	PECVD method for producing ultra low-k dielectric films using UV treatment	WU, QINGGUO
<u>60949204</u>	Not Issued	20	07/11/2007	METHODS FOR FABRICATING ZEOLITE NANO-CRYSTAL BASED LOW-K DIELECTRIC FILMS CONTAINING Si(C _x H _y) _n GROUPS AND TREATING FILMS BY ULTRA-VIOLET THERMAL PROCESSING	WU, QINGGUO

Inventor Search Completed: No Records to Display.

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Inventor Name Search Result

Your Search was:

Last Name = FU

First Name = HAIYING

Application#	Patent#	Status	Date Filed	Title	Inventor Name
10099232	6764952	150	03/13/2002	SYSTEMS AND METHODS TO RETARD COPPER DIFFUSION AND IMPROVE FILM ADHESION FOR A DIELECTRIC BARRIER ON COPPER	FU, HAIYING
10184681 200301-7081	6777349	150	06/28/2002	HERMETIC SILICON CARBIDE	FU, HAIYING
10334350 <i>-du JDS</i>	6855645	150	12/30/2002	SILICON CARBIDE HAVING LOW DIELECTRIC CONSTANT	FU, HAIYING
10672311 <i>JDS</i>	7208389	150	09/26/2003	METHOD OF POROGEN REMOVAL FROM POROUS LOW-K FILMS USING UV RADIATION	FU, HAIYING
10789103 <i>JDS</i>	Not Issued	41	02/27/2004	Methods for producing low-k CDO films with low residual stress	FU, HAIYING
10800409 <i>JDS</i>	Not Issued	100	03/11/2004	METHODS FOR PRODUCING LOW-K CDO FILMS	FU, HAIYING
10807680	Not Issued	30	03/23/2004	Methods of porogen removal for porous low dielectric constant films using plasma treatments	FU, HAIYING
10820525 <i>JDS</i>	Not Issued	41	04/07/2004	Methods for producing low-k CDO films with low residual stress	FU, HAIYING
10825888 <i>JDS</i>	7253125	150	04/16/2004	METHOD TO IMPROVE MECHANICAL STRENGTH OF LOW-K DIELECTRIC FILM USING MODULATED UV EXPOSURE	FU, HAIYING
10860340 <i>JDS</i>	7094713	150	06/02/2004	METHODS FOR IMPROVING THE CRACKING RESISTANCE	FU, HAIYING

				OF LOW-K DIELECTRIC MATERIALS	
<u>10869474</u>	<u>7282438</u>	150	06/15/2004 JDS	LOW-K SIC COPPER DIFFUSION BARRIER FILMS	FU, HAIYING
<u>10927777</u> <i>JDS</i>	<u>7241704</u>	150	08/27/2004	METHODS FOR PRODUCING LOW STRESS POROUS LOW-K DIELECTRIC MATERIALS USING PRECURSORS WITH ORGANIC FUNCTIONAL GROUPS	FU, HAIYING
<u>10941502</u> <i>JDS</i>	Not Issued	99	09/14/2004	METHODS FOR IMPROVING INTEGRATION PERFORMANCE OF LOW STRESS CDO FILMS	FU, HAIYING
<u>10982654</u> <i>JDS</i>	Not Issued	30	11/05/2004	Methods of improving porogen removal and film mechanical strength in producing ultra low-k carbon doped oxide films using radical photopolymerization	FU, HAIYING
<u>11369658</u> <i>JDS</i>	Not Issued	30	03/06/2006	Methods for fabricating high hardness/modulus low dielectric constant materials	FU, HAIYING
<u>11376510</u>	Not Issued	93	03/14/2006	METHODS FOR IMPROVING THE CRACKING RESISTANCE OF LOW-K DIELECTRIC MATERIALS	FU, HAIYING
<u>11693661</u> <i>JDS</i>	Not Issued	30	03/29/2007	METHODS FOR IMPROVING PERFORMANCE OF ODC FILM WITH DIELECTRIC CONSTANT < 4.0	FU, HAIYING
<u>11764750</u>	Not Issued	41	06/18/2007	METHODS FOR PRODUCING LOW STRESS POROUS LOW-K DIELECTRIC MATERIALS USING PRECURSORS WITH ORGANIC FUNCTIONAL GROUPS	FU, HAIYING
<u>11824049</u>	Not Issued	30	06/28/2007	Method to improve mechanical strength of low-K dielectric film using modulated UV exposure	FU, HAIYING
<u>11893490</u>	Not Issued	25	08/15/2007 ?	Low-k sic copper diffusion barrier films	FU, HAIYING
<u>11936752</u>	Not Issued	19	01/01/0001	METHODS FOR IMPROVING INTEGRATION PERFORMANCE OF LOW STRESS CDO FILMS	FU, HAIYING
<u>11936754</u>	Not	19	01/01/0001	METHODS FOR PRODUCING	FU, HAIYING

	Issued			LOW-K CDO FILMS	
60524330	Not Issued	159	11/20/2003	Methods for producing low-k CDO film of low residue stress with dielectric constant < 3.0	FU, HAIYING

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Inventor Name Search Result

Your Search was:

Last Name = MUIR

First Name = TIMOTHY

Application#	Patent#	Status	Date Filed	Title	Inventor Name
10807680	Not Issued	30	03/23/2004	Methods of porogen removal for porous low dielectric constant films using plasma treatments	MUIR, TIMOTHY J.

Inventor Search Completed: No Records to Display.

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